

Maarten van Es, Laurent Fillinger, and Hamed Sadeghian NOMI, TNO, Delft, The Netherlands

innovation for life





VISION & MISSION

NOMI ecosystem is setup based on the following vision of the future:

We see a future where humanity will solve many of future's challenges in data, energy and life sciences by a continuous miniaturization in device fabrication down to an atomic scale

The NOMI-ecosystem develops the technologies that enable exploration and exploitation of the atomscale world level leading to the real-world applications

The NOMI-ecosystem research to create the **instruments to image**, **measure and fabricate devices at the level of individual atoms** at an humanly acceptable and economically attractive level





- **About NOMI**
- > SPM platforms
- > SPM modalities for metrology
- Scanning Subsurface Probe Microscopy
- Technical background
- Application possibilities
- Quantifying SSPM: hurdles and solutions (see also next talk!)
- > Results



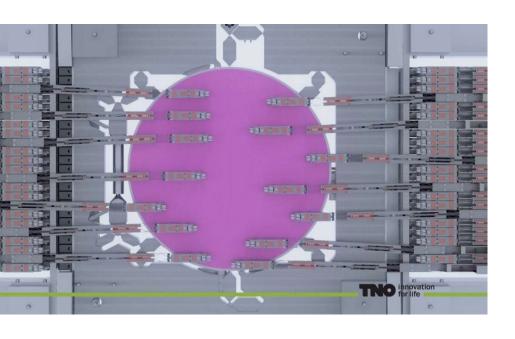


- **NOMI SPM Platforms:**
- High Throughput SPM
- Large Dynamic Range SPM
- NOMI SPM modalities
- High Aspect Ratio
- SubSurface SPM
- Nanolithography
- NEW: Chemical Characterization (hydrophobicity)

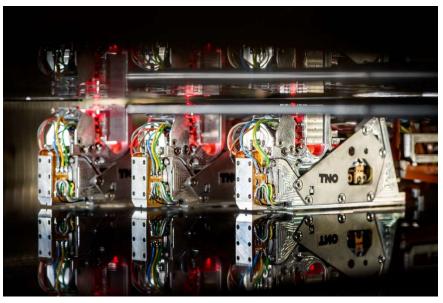




- NOMI SPM Platforms:
- > High Throughput SPM
 - fully automated
 - in- or near-line inspection
- Large Dynamic Range SPM



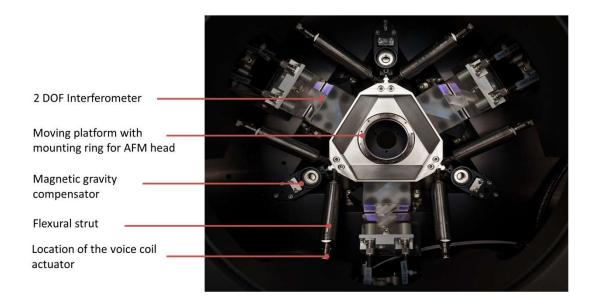








- **NOMI SPM Platforms:**
- High Throughput SPM
- Large Dynamic Range SPM
 - sub-nm precision over mm distances
 - verlay distance between product features and markers
 - > characterizing abberations across a full die



Poster: 10959-85

First results from the Large Dynamic Range Atomic Force Microscope for overlay metrology

G. Witvoet, J. Peters, S. Kuiper, A. Keyvani, R. Willekers

TNO -Optomechatronics department P.O. Box 155, 2600 AD, Delft, The Netherlands Gert wityget@tno.ni



TNO is developing a novel Large Dynamic Range Atomic Force Microscope (LDR-AFM). The current work provides an overview of recent developments and presents the first results obtained after final integration of the complete system.

The LDR-AFM combines a highly accurate long-

stroke interferometric 6-DoF motion stage with a sub-ron. AFM measurement, head, enabline measurements of sub-nm features on a wafer over multiple millimeters marker-to-feature distances (Figure 1)



House 1: System overview of the LDR ARM. The 6-DOF hexagod positioning stage (Figure probe with respect to the sample substrate. In the hexapod stage, an AFM head (Figure 3) is mounted that scans the product and marker features. The APM head is easily emovable from the stage and is designed for low power dissipation, and high stability



Figure 2: LDR-AFM head mountable

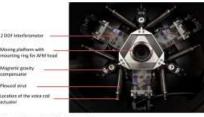


Figure 1: Hexapod stage in the LDR-AFM

In the current work, first results from the LOB-APM are presented. With the integrated APM measurement head the first APM characterization measurements are performed. Deflection distance curves are measured (Figure 4), and confirm the expectations on low noise levels a correct AFM head functionality. Furthermore, control relevant identification is performed to knearity of the bp-sample and cantilever dynamics (Figure 4). Fight reproducibility for varying setpoints indicate strong linearity. Furthermore, a measured line topology is illustrated on the Finally long-term drift is assessed by measuring the interferometer signals over multiple hou closed loop. (Figure 5), showing impressive stability and indicating < 50 pm/min drift

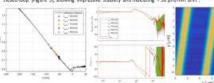
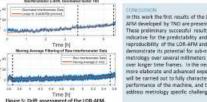


Figure 4: LDR-AFM Deflection distance curve and identification (left). Topology image [rigl



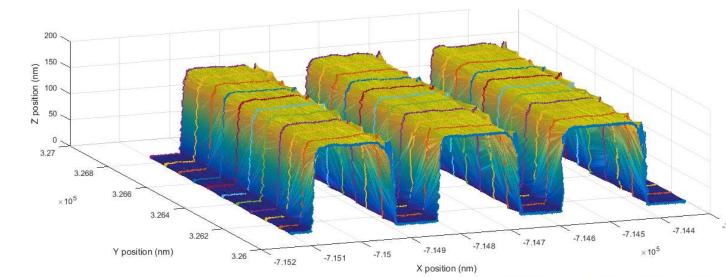
APM developed by TND are present These preliminary successful result indicative for the predictability and reproducibility of the LOR AFM and metrology over several millimeters more elaborate and advanced exec will be carried out to fully characte performance of the machine, and t address metrology specific challeng

2 1 Titol van deze uitgave





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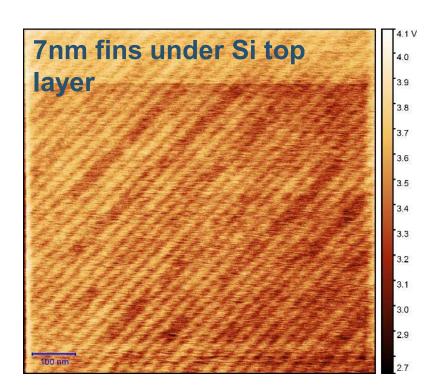


87 degrees sidewall angle! 150 nm feature height





- **NOMI SPM Platforms:**
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- > SubSurface SPM
 - > CD
 - alignment
 - > overlay
 - defect review
- Nanolithography
- NEW: Chemical Characterization (hydrophobicity)

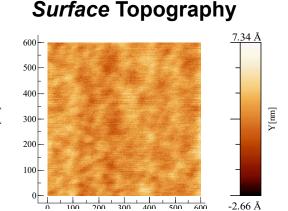


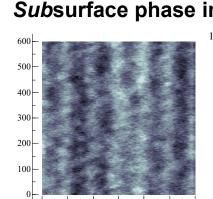




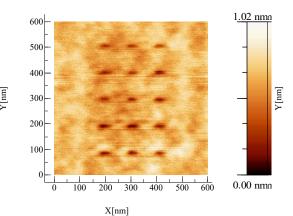
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 - contact holes
- NEW: Chemical Characterization (hydrophobicity)

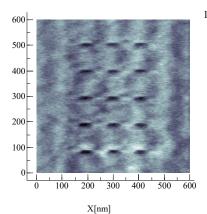
Before drilling









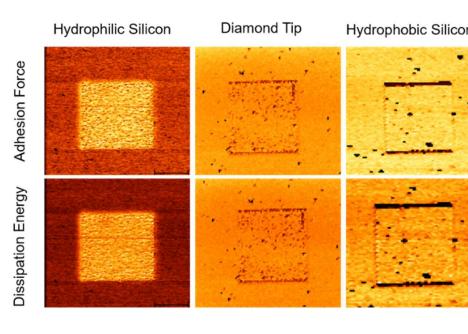


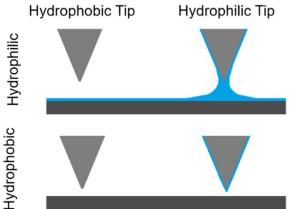
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- SubSurface SPM
- Nanolithography
- NEW: Chemical Characterization
 -) low k materials (hydrophobicity)
 - > characterization of contaminations
 - > ...?







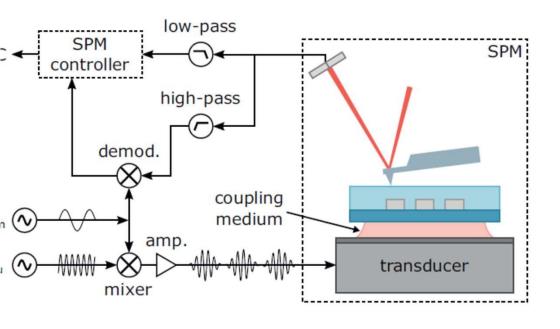


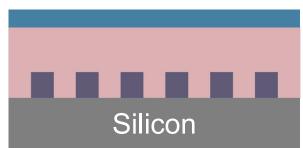
QUANTITATIVE SUBSURFACE SCANNING PROBE MICROSCOPY

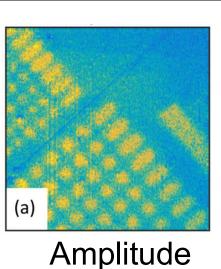
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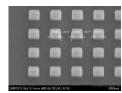


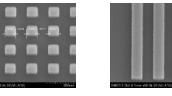


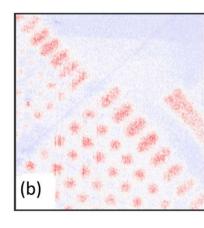












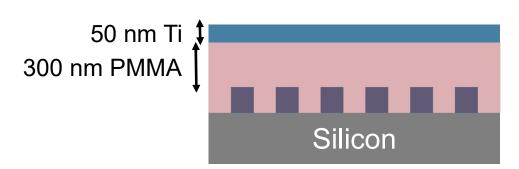
Phase

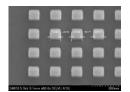
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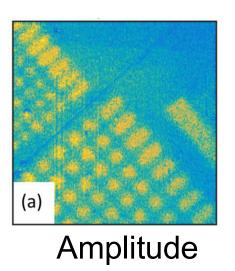


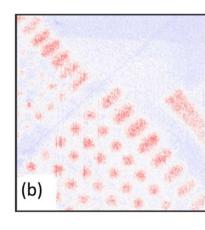
- SSPM Achievements
 - Imaging of deep structures
 - Imaging of small structures
 - Imaging of defects









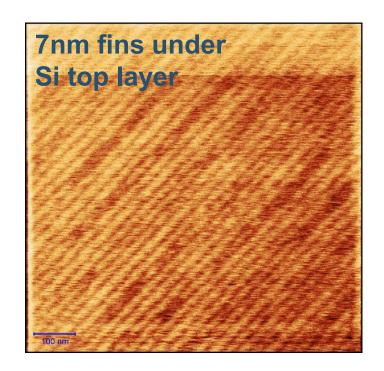


Phase





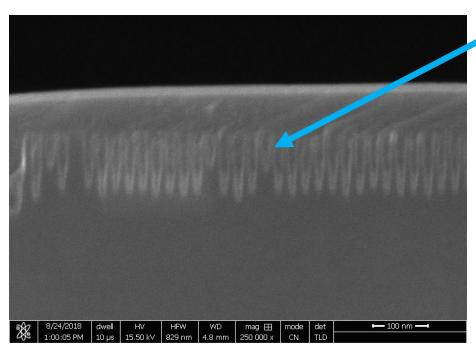
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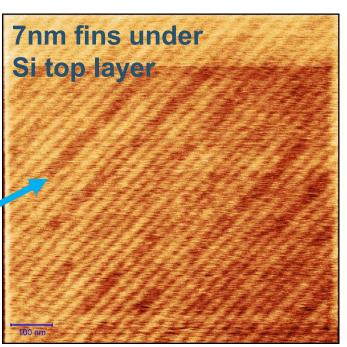






- SSPM Achievements
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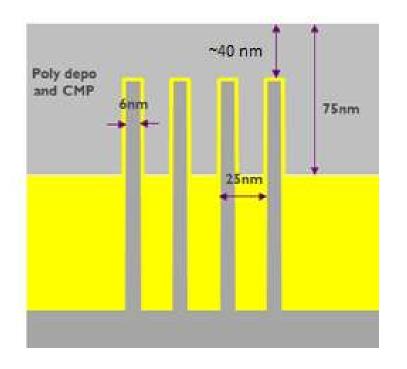


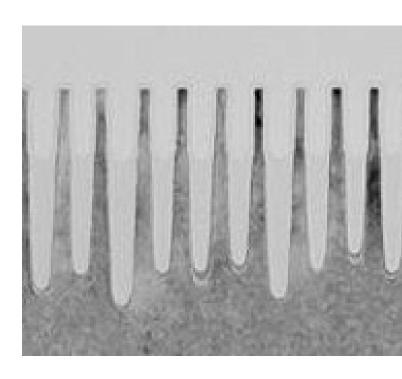




How to obtain Critical Dimensions from SSPM data?

Combine Finite Element Modeling with quantifiable measurements



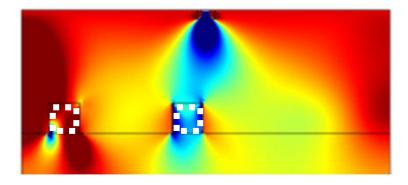






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Combine Finite Element Modeling with quantifiable measurements



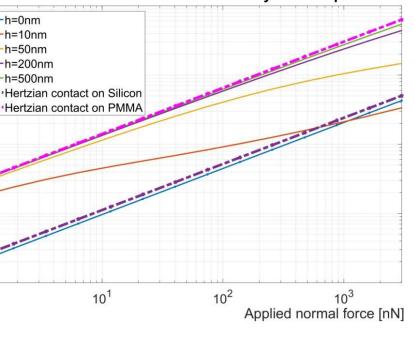


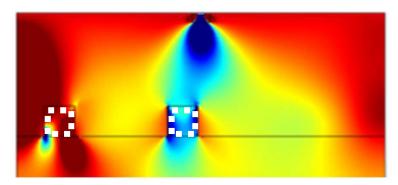


How to obtain Critical Dimensions from SSPM data?

Combine Finite Element Modeling with quantifiable measurements

Simulated Hertzian contact on layered sample







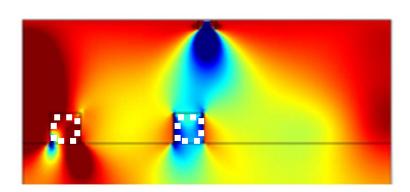


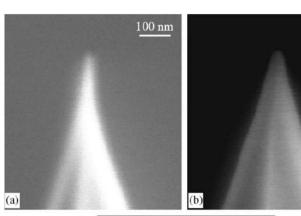
How to obtain Critical Dimensions from SSPM data?

Combine Finite Element Modeling with quantifiable measurements

h=0nm h=10nm h=50nm h=200nm h=50nm Hertzian contact on Silicon Hertzian contact on PMMA 10² Applied normal force [nN]

Simulated Hertzian contact on layered sample





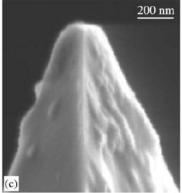


Fig. 2. SEM images of brand new tips revealing the wide of possible new-tip geometry. The scale is the same for all three Sharp tip with radius of curvature R < 10 nm.(b) Tip with R < 10 mm.(b) Very blunt tip with possible surface contamination not seen in



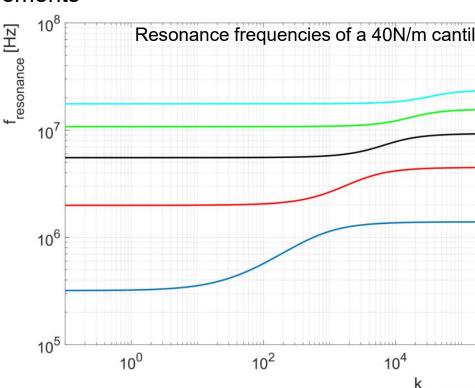


How to obtain Critical Dimensions from SSPM data?

Combine Finite Element Modeling with quantifiable measurements

Euler Bernoulli beam equation:

$$rac{\partial^2}{\partial x^2}\left(EIrac{\partial^2 w}{\partial x^2}
ight) = -\murac{\partial^2 w}{\partial t^2} + q(x)$$







Boundary	w"	w"	w'	w
Clamp			Δw ' = 0*	Δw = 0 *
Simple support		$\Delta w'' = 0$	Δw ' = 0	Δw = 0 *
Point force	Δw ''' = λ	$\Delta w'' = 0$	∆w ′ = 0	Δw = 0
Point torque	Δw " = 0	∆w" = т	Δw ' = 0	$\Delta w = 0$
Free end	w''' = 0	w'' = 0		
Clamp at end			w' fixed	w fixed
Simply supported end		w" = 0		w fixed
Point force at end	$w''' = \pm \lambda$	w" = 0		
Point torque at end	w''' = 0	$w'' = \pm \tau$		





How to obtain Critical Dimensions from SSPM data?

Combine Finite Element Modeling with quantifiable measurements

Iow-pass

SPM
controller

high-pass

demod.

f_m

whigh-pass

representation to the coupling medium amp.

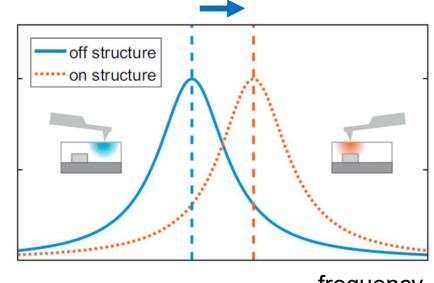
f_u

whigh-pass

transducer

mixer

Next talk: How to measure Δf_{re} and how not to have a transduction below the wafer



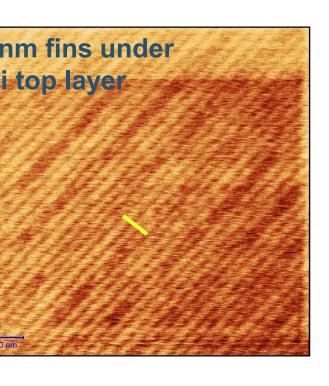
Amplitude

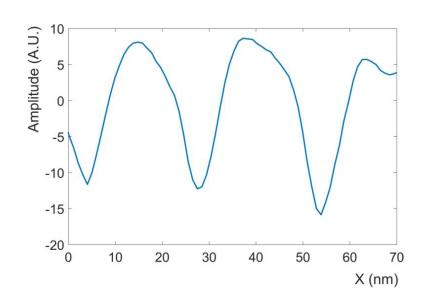
frequency

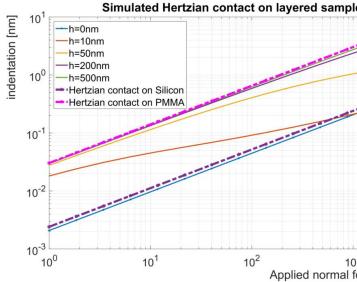




PRELIMINARY RESULTS











CONCLUSIONS

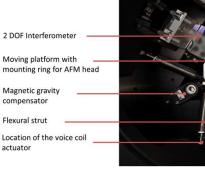
NOMI brings a range of platforms and modalities for SPM to solve manufacturing challenges in semiconductor applications

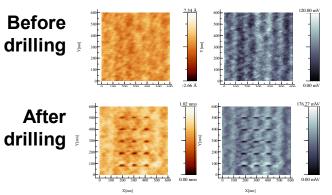
SubSurface Probe Microscopy visualizes structures under layers of arbitrary materials with high resolution

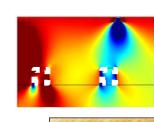
Suitable for alignment, overlay and defect characterization applications

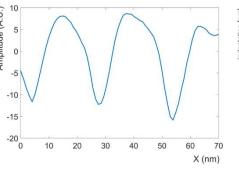
SubSurface Probe Microscopy can also extract structural parameters such as CD height or width

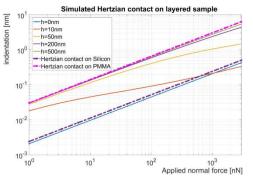
















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